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Erratum: "Nonvolatile and unipolar resistive switching characteristics of pulsed laser ablated NiO films" [J. Appl. Phys. 108, 104513 (2010)]

D. Panda, A. Dhar, and S. K. Ray[a)]
Department of Physics and Meteorology, Indian Institute of Technology Kharagpur, Kharagpur, India, 721 302

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In the original published version of this article, Eq. (1) and the unit of the x-axis in Fig. 9(a) are incorrect. The rectified equation and figure are given below.

$$\ln(J/E)\sim -q\phi_b-\left(\frac{\sqrt{q^3/\pi\varepsilon_r\varepsilon_o}.\sqrt{E}}{\lambda k_B T}\right) \tag{1}$$

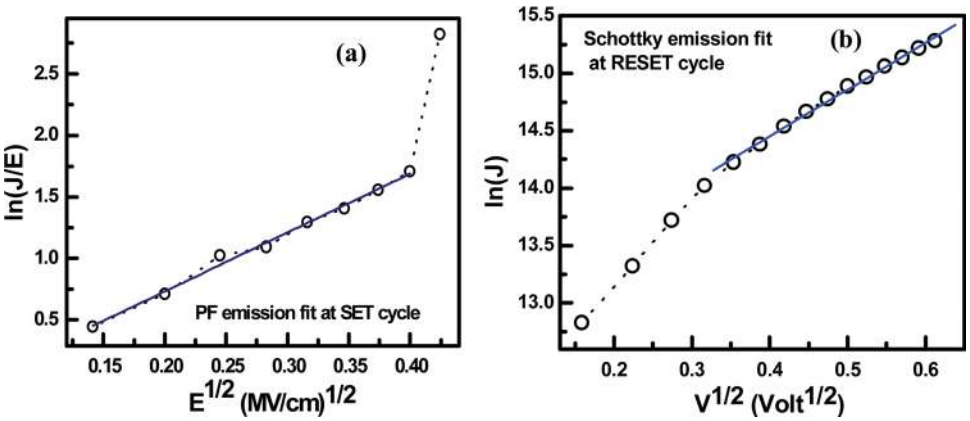

FIG. 9. (Color online) Curve fitting plots for applying (a) Schottky (LRS) and (b) Poole-Frenkel (HRS) emissions of the I-V characteristics presented in Fig. 8(a).

[a)]Author to whom correspondence should be addressed. Electronic addresses: dpanda@phy.iitkgp.ernet.in; physkr@phy.iitkgp.ernet.in.

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